

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments
1	BRS	L1	129 280	(polymer\$3 or residue or stringers) same (NH3 or ammonia or hydrogen or H2)	USP AT	2002/0 3/15 13:07	
2	IS& R	L2	318 7	(156/345).CCLS.	USP AT	2002/0 3/15 13:07	
3	BRS	L3	76	1 and 2	USP AT	2002/0 3/15 13:35	
4	BRS	L7	123 612	(photoresist or resist) and (opening or via)	USP AT; EPO ; JPO ; IBM TD B	2002/0 3/15 14:54	
5	BRS	L8	452 3	1 and 7	USP AT; EPO ; JPO ; IBM TD B	2002/0 3/15 13:38	
6	BRS	L9	98	8 and chuck and chamber	USP AT; EPO ; JPO ; IBM TD B	2002/0 3/15 13:42	
7	BRS	L1 0	164 2	8 and (etch\$4 or getter\$4)	USP AT; EPO ; JPO ; IBM TD B	2002/0 3/15 13:43	

	Typ e	L #	Hit s	Search Text	DBs	Time Stamp	Comme nts
8	BRS	L1 1	983	@pd<=19990891 and 10	USP AT; EPO ; JPO ; IBM _TD _B	2002/0 3/15 13:44	
9	BRS	L1 2	542	11 and semiconductor	USP AT; EPO ; JPO ; IBM _TD _B	2002/0 3/15 13:45	
10	BRS	L1 6	602	hydrocarbons same polymer\$3 same plasma	USP AT; EPO ; JPO ; IBM _TD _B	2002/0 3/15 15:08	
11	IS& R	L1 7	118 2	((438/706) or (438/710) or (438/712) or (438/714)).CCLS.	USP AT	2002/0 3/15 15:09	
12	BRS	L1 8	13	16 and 17	USP AT; EPO ; JPO ; IBM _TD _B	2002/0 3/15 15:18	
13	BRS	L2 1	205	polymer same clean\$4 same ("CO.sub.2" or "carbon dioxide")	USP AT	2002/0 3/15 15:26	
14	BRS	L2 4	1	6200412.pn.	USP AT	2002/0 3/15 15:39	